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Morphological and optical properties of aluminum nanoparticles deposited by thermal evaporation on heated substrates

Ines Lachebi ¹, Abdelkrim Fedala ^{1,*}, Thierry Djenizian ², Toufik Hadjersi ³, Mohamed Kechouane ¹

Abstract

In the present work, aluminum nanoparticles (AI-NPs) are deposited by thermal evaporation on heated substrates without additional annealing process after deposition on silicon (100) and corning glass. Their morphological and optical properties are investigated by Scanning Electron Microscopy (SEM), Atomic Force Microscope (AFM), and Optical Transmission Technique. The substrate temperature was varied from 200 to 580 °C and the mass thickness between 4 and 23 nm. AI-NPs are well formed in all deposition temperatures with a mass thickness of 15 nm in one-step. The mean diameter of AI-NPs rises from 50 to 91 nm as the deposition temperature increases from 200 to 500 °C, and then it remains nearly unchanged in the range of 500-580 °C. When the mass thickness increases from 4 to 23 nm at 400 °C deposition temperature, the NPs size increases from 15 to 135 nm. The NPs turn into irregular in shape and their coverage density increases strongly. Under some conditions, the AI-NPs exhibit a broad absorption in the near ultraviolet range. This is attributed to the Localized Surface Plasmon Resonances (LSPRs) absorption. The deposition temperature and the aluminum mass thickness are the key parameters for controlling the AI-NPs size. Based on

¹ USTHB, Faculté de Physique, Laboratoire de physique des matériaux, Equipe Couches Minces et Semiconducteurs, B.P. 32, El Alia, 16111 Bab-ezzouar, Algers, Algeria.

² MADIREL, UMR7246- Université d'Aix-Marseille, Campus Scientifique de St. Jérôme F-13397 Marseille Cedex 20, France.

³ Research Center of Semiconductor Technology for Energy-2, Bd Frantz Fanon, BP 140, Alger 7 Merveilles 16038, Algers, Algeria.

^{*} Corresponding author: Abdelkrim Fedala. Postal address: USTHB, Faculté de Physique, Laboratoire de physique des matériaux, Equipe Couches Minces et Semiconducteurs, B.P. 32, El Alia, 16111 Bab-ezzouar, Algers, ALGERIA. E-mail address: afedala@usthb.dz. Tel/Fax: 00 213 21 24 75 28

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